Short Bunch Beam Profiling

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Abstract

The complete longitunal profiling of short electron bunches is discussed in the context of 4th generation light sources. The high peak current required for the SASE lasing process is achieved by longitudinal compression of the electron bunch. The lasing process also depends on of the preservation of the transverse emittance along the bunch during this manipulation in longitudinal phase space. Beam diagnostic instrumentation needs to meet several challenges: The bunch length and longitudinal profile should be measured on a single bunch to characterize the instantaneous, peak current along the bunch. Secondly, the transverse emittance and longitudinal energy spread should be measured for slices of charge along the bunch. Several techniques for invasive and noninvasive bunch profiling will be reviewed, using as examples recent measurements from the SLAC Sub Picosecond Photon Source (SPPS) and the planned diagnostics for the Linac Coherent Light Source (LCLS). These include transverse RF deflecting cavities for temporal streaking of the electron bunch, RF zero-phasing techniques for energy correlation measurements, and electro-optic measurements of the wakefield profile of the bunch.

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